



**2nd Announcement and
Call for Papers
304th PTB-Seminar
VUV and EUV Metrology**



On **October 19 and 20, 2017**, the 304th PTB Seminar "VUV and EUV Metrology" will take place at the "Hermann von Helmholtz Building" at the Berlin-Charlottenburg campus of PTB. This seminar, the fourth in a series launched in 2011, is a forum for interdisciplinary exchange between basic and technology-oriented researchers and industrial users. Invited and submitted lectures as well as a poster session will be presented. The topics cover latest results from industrial applications of EUV radiation for lithography and measurement technology to developments for space-based VUV and EUV spectroscopy and the investigation of nano-structured surfaces. The implementation is supported by the Helmholtz-Fonds e.V.

Invited speakers (confirmed):

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| ■ V. Banine, ASML (NL) | ■ T. Tanaka, NMIJ/AIST (JP) | ■ J. Larruquert, IFA-CSIC (ES) |
| ■ H. Enkisch, Carl Zeiss SMT (DE) | ■ R. Ivanov, DESY (DE) | ■ L. Gavilan, LATMOS (FR) |
| ■ I. Englard, AMIL (IL) | ■ J.-P. Halain, CSL (BE) | ■ N. Papathanasiou, sglux (DE) |
| ■ T. Feigl, optiXfab (DE) | ■ K. Moshhammer, PTB (DE) | |

Submissions of oral and poster contributions are welcome. **The submission deadline is July 1st.**

Please use our website for submissions: <http://www.euv2017.ptb.de/euv2017-home.html>

Topics covered:

- EUV Lithography
Achievements and challenges in the implementation of EUV lithography in the semiconductor production
- EUV Scattering
Application of EUV and soft X-ray scattering in the analysis of nano-structured surfaces, structures on wafer, functionalized surfaces, self-assembled polymers and others
- Surface Characterization
VUV and EUV reflectometry and ellipsometry, grazing incidence spectroscopy with soft X-ray, quantitative electron spectroscopy, imaging methods
- Space instruments
VUV and EUV instrumentation for space based astronomy, calibration and reliability of instruments
- Detectors
Detector concepts for the VUV and EUV spectral ranges, imaging detectors, solar-blind detectors, detector calibration, characterization, and life time studies
- Instrumentation and Optics
Laboratory based and synchrotron-radiation instrumentation for VUV and EUV applications, new concepts of optical elements like multilayer-gratings and -Laue lenses as well as high-reflectance normal incidence multilayer optics for the water window and beyond
- Sources
Laboratory based sources for the VUV to soft X-ray spectral range for applications in metrology as well as high-power generation for lithography

Sponsored by



Sponsoring contributions for the organization of the seminar are appreciated. For details please contact us:
<https://www.euv2017.ptb.de/euv2017-contact.html>

